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(54) Title: A METHOD OF BONDING BY MOLECULAR BONDING

(57) Abstract: A method of bonding by molecular bonding between at least one lower wafer (20) and an upper wafer (30) comprises positioning the upper wafer on the lower wafer. In accordance with the invention, a contact force (F) is applied to the peripheral side (22, 32) of at least one of the two wafers (30, 20) in order to initiate a bonding wave between the two wafers.

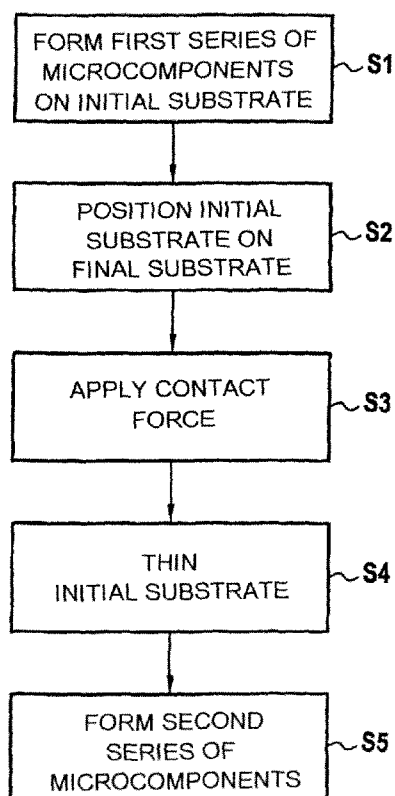


FIG.7



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